

ABSTRACT OF THE DISCLOSURE

A semiconductor device manufacturing system for manufacturing a semiconductor device on a wafer, comprising: a first exposure apparatus for exposing the wafer using a light source while moving the wafer with a predetermined interval; and a second exposure apparatus for exposing the wafer by irradiating a plurality of electron beams on the wafer, the plurality of electron beams having an interval of substantially N times or $1/N$ times, where N is a natural number, of the predetermined interval.

10

FOI 60459560